

	Hits	Search Text	DBs
75	6	((EUV or UV or VUV or DUV or X\$2ray or ultraviolet or light) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near22 (resist or photoresist) near20 (pattern) near29 strip\$4 near29 (remov\$5)) and (((resist or photoresist) near12 (residu\$3 or remain\$4) near24 (light or UV or EUV or DUV or X\$3ray or VUV or ultraviolet) near39 (irradiat\$4 or illuminat\$4 or imping\$4 or expos\$4)) same develop\$4) and (metal\$3 near22 etch\$4 near24 pattern)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
76	4	((EUV or UV or VUV or DUV or X\$2ray or ultraviolet or light) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near22 (resist or photoresist) near20 (develop\$4 or pattern) near29 etch\$4 near26 (metal\$4 or conductive)) and (((resist or photoresist or photosensitive) near14 pattern near12 strip\$4 near29 (remov\$5)) and (((resist or photoresist) near12 (residu\$3 or remain\$4) near24 (light or UV or EUV or DUV or X\$3ray or VUV or ultraviolet) near39 (irradiat\$4 or illuminat\$4 or imping\$4 or expos\$4)) same develop\$4) and (metal\$3 near22 etch\$4 near24 pattern)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
77	0	430/165.ccls. and ((EUV or UV or VUV or DUV or X\$2ray or ultraviolet) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near22 (resist or photoresist) near20 (pattern) near29 strip\$4 near29 (remov\$5)) and (((resist or photoresist) near12 (residu\$3 or remain\$4)) near26 (UV or EUV or DUV or X\$3ray or VUV or ultraviolet) near22 (irradiat\$4 or illuminat\$4 or imping\$4 or expos\$4) near29 develop\$4) and quinone	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
78	0	430/326.ccls. and ((EUV or UV or VUV or DUV or X\$2ray or ultraviolet) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near22 (resist or photoresist) near20 (pattern) near29 strip\$4 near29 (remov\$5)) and (((resist or photoresist) near12 (residu\$3 or remain\$4)) near26 (UV or EUV or DUV or X\$3ray or VUV or ultraviolet) near22 (irradiat\$4 or illuminat\$4 or imping\$4 or expos\$4) near29 develop\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
79	1	430/328.ccls. and ((EUV or UV or VUV or DUV or X\$2ray or ultraviolet) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near22 (resist or photoresist) near20 (pattern) near29 strip\$4 near29 (remov\$5)) and (((resist or photoresist) near12 (residu\$3 or remain\$4)) near26 (UV or EUV or DUV or X\$3ray or VUV or ultraviolet) near22 (irradiat\$4 or illuminat\$4 or imping\$4 or expos\$4) near29 develop\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
80	2	430/318.ccls. and ((EUV or UV or VUV or DUV or X\$2ray or ultraviolet) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near22 (resist or photoresist) near20 (pattern) near29 strip\$4 near29 (remov\$5)) and (((resist or photoresist) near12 (residu\$3 or remain\$4)) near26 (UV or EUV or DUV or X\$3ray or VUV or ultraviolet) near22 (irradiat\$4 or illuminat\$4 or imping\$4 or expos\$4) near29 develop\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
81	2	430/313.ccls. and ((EUV or UV or VUV or DUV or X\$2ray or ultraviolet) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near22 (resist or photoresist) near20 (pattern) near29 strip\$4 near29 (remov\$5)) and (((resist or photoresist) near12 (residu\$3 or remain\$4)) near26 (UV or EUV or DUV or X\$3ray or VUV or ultraviolet) near22 (irradiat\$4 or illuminat\$4 or imping\$4 or expos\$4) near29 develop\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
82	0	430/329.ccls. and ((EUV or UV or VUV or DUV or X\$2ray or ultraviolet) near22 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near22 (resist or photoresist) near20 (pattern) near29 strip\$4 near29 (remov\$5)) and (((resist or photoresist) near12 (residu\$3 or remain\$4)) near26 (UV or EUV or DUV or X\$3ray or VUV or ultraviolet) near22 (irradiat\$4 or illuminat\$4 or imping\$4 or expos\$4) near29 develop\$4)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB